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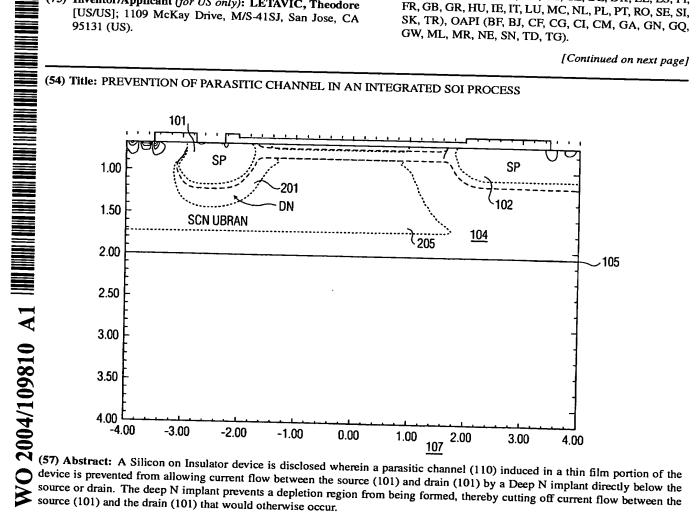
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- (71) Applicant (for all designated States except US): KONIN-KLIJKE PHILIPS ELECTRONICS N.V. [NL/NL]; Groenewoudseweg 1, NL-5621 BA Eindhoven (NL).
- (72) Inventor; and
- (75) Inventor/Applicant (for US only): LETAVIC, Theodore [US/US]; 1109 McKay Drive, M/S-41SJ, San Jose, CA 95131 (US).

- (74) Agent: KONINKLIJKE PHILIPS ELECTRON-ICS N.V.; c/o LESTER, Shannon, 1109 McKay Drive, M/S-41SJ, San Jose, CA 95131 (US).
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device is prevented from allowing current flow between the source (101) and drain (101) by a Deep N implant directly below the source or drain. The deep N implant prevents a depletion region from being formed, thereby cutting off current flow between the source (101) and the drain (101) that would otherwise occur.

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## Declaration under Rule 4.17:

as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii)) for the following designations AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW, ARIPO patent (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,

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